	Search Terms
1	CARLOS-VINCENT-J
2	DORAN-JAMES-E
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7	МАСНІА-КЕІТН- Э
8	RESIST
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10	SUNDLING-DIANNE-L
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12	(((((((BOWLEY-REGINALD-R.IN.) OR (CARLOS-VINCENT-).IN.)) OR (DORAN-JAMES-E.IN.)) OR (SHAVER-JOSEPH-E.IN.)) OR (MACHIA-KEITH-J.IN.)) OR (SUNDLING-DIANNE-L.IN.)) OR (KNIGHT-STEPHEN-E.IN.)) OR (LEIDY-ROBERT-K.IN.)) AND FOCUS AND RESIST)

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11	72739							
12	20	17	3	0	0	0	0	

	>	 Document ID	Issue Date	Pages	Title	Current OR
		US 20030158710 A1	20030821	26	Contact hole profile and line edge width metrology for critical image control and feedback of lithographic focus	702/189
2	☒	US 20030091907 A1	20030515	7	Reverse tone process for masks	430/5
3	×	US 20010021577 A1	20010913	4	METHOD FOR FORMING SIDEWALL SPACERS USING FREQUENCY DOUBLING HYBRID RESIST AND DEVICE FORMED THEREBY	438/595
4	⊠	US 6420766 B1	20020716		Transistor having raised source and drain	257/401
5	⊠	US 6303416 B1	20011016		Method to reduce plasma etch fluting	438/166
9		US 6278515 B1	20010821		Method and apparatus for adjusting a tilt of a lithography tool	355/55
7	⊠	US 6255178 B1	20010703		Method for forming transistors with raised source and 438/300 drains and device formed thereby	438/300
8	Ø	US 6232639 B1	20010515		Method and structure to reduce latch-up using edge implants	257/372
6	⊠	US 6218704 B1	20010417		ESD protection structure and method	257/355

11/06/2003, EAST Version: 1.4.1

	Current XRef	Retrieval Classif	Inventor	s	ပ	۵	2	м	4	ß	Image Doc. Displayed	ᆸ
1			Bowley, Reginald R. JR. et al.	Ø							US 20030158710	
2	430/322; 430/324		Horak, David V. et al.								US 20030091907	
æ	257/E21.027; 257/E21.252; 257/E21.257; 257/E21.435; 257/E21.437		BROWN, JEFFREY S. et al.					. 🗆			US 20010021577	
4	257/327; 257/622; 257/E21.027; 257/E21.252; 257/E21.435; 257/E21.435		Brown, Jeffrey S. et al.								US 6420766	
2	438/942		Bruce, James A. et al.								US 6303416	
9	250/216; 250/492.2; 250/492.22; 355/53; 355/77; 430/30; 430/311; 430/314;		Knight, Stephen E. et al.								US 6278515	
7	257/E21.027; 257/E21.252; 257/E21.257; 257/E21.435; 257/E21.437; 438/303		Brown, Jeffrey S. et al.								US 6255178	
∞	257/519; 257/E21.642; 257/E27.063		Baker, Faye D. et al.								US 6232639	
6	257/356; 257/358; 257/359; 257/546; 257/E29.063		Brown, Jeffrey S. et al.								US 6218704	

Current OR	ate 438/743	gions 257/506) and ,,,,,,	430/31 2	43 <i>u</i> /31 <i>z</i>	dge 438/232
Title	Method for forming cornered images on a substrate and photomask formed thereby	Method of photolithographically defining three regions with one mask step and self aligned isolation structure formed thereby	Method for forming transistors with raised source and 430/312 drains and device formed thereby		Method and structure to reduce latch-up using edge implants	Method and structure to reduce latch-up using edge implants Method for forming sidewall spacers using frequency doubling hybrid resist and device formed thereby
Pages	26 me	Me 43 wit	43 drs		37 me	
Issue Date	20010206	20001114 4	20000808		20000307	
Document ID	US 6184151 B1	US 6147394 A	US 6100013 A		US 6033949 A	US 6033949 A
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	10	11	12	-	13	

11/06/2003, EAST Version: 1.4.1

	Current XRef	Retrieval Classif	Inventor	s	C	۵	2	3	4	2	Image Doc. Displayed	ᆸ
10	257/E21.035; 257/E21.036; 257/E21.652; 438/717; 438/736; 438/737; 438/738;		Adair, William J. et al.								US 6184151	
11	257/641; 257/649; 257/E21.545		Bruce, James A. et al.								US 6147394	
12	216/46; 257/E21.027; 257/E21.252; 257/E21.257; 257/E21.435; 257/E21.437; 430/314; 438/303		Brown, Jeffery S. et al.								US 6100013	
13	148/DIG.137; 257/E21.642; 257/E27.063; 438/223; 438/227		Baker, Faye D. et al.								US 6033949	
14	257/E21.027; 257/E21.252; 257/E21.257; 257/E21.435; 257/E21.437; 430/312; 430/313; 430/316;		Brown, Jeffrey S. et al.								US 5981148	
15	257/E21.027; 257/E21.252; 257/E21.257; 257/E21.435; 257/E21.437; 430/316; 438/445; 438/696		Brown, Jeffrey S. et al.								US 5976768	

1 Document ID Issue Date Pages	Issue Date Pages	Pages			Title	Current OR
Method of photolithograp Method of photolit	19991026 44	4		Method of photolith with one mask step structure formed the	hically defining three regions self aligned isolation	430/314
Method for forming cornered im	US 5959325 A 19990928 27	27		Method for forming and photomask for	ages on a substrate	257/302
□ US 5939767 A 19990817 36 CMOS	19990817 36	36		Structure and proc CMOS	ation in	257/551
□ US 5882967 A 19990316 36 Process for buried or second control or second c	US 5882967 A 19990316 36 Prα	36	ğ	Process for buried o		438/237
	US 5861330 A 19990119 37	37		Method and struc implants	dge	438/232

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16	257/E21.545; 430/313; 430/317		Bruce, James A. et al.								US 5972570	
17	257/E21.035; 257/E21.036; 257/E21.652; 438/387; 438/942		Adair, William J. et al.								US 5959325	
18	257/355; 257/481; 257/603; 257/E21.632		Brown, Jeffrey S. et al.								US 5939767	
19	257/E21.632; 430/270.1; 430/325; 430/326; 438/200;		Brown, Jeffrey S. et al.								US 5882967	
70	257/E21.642; 257/E27.063; 430/311; 438/223; 438/227; 438/529		Baker, Faye D. et al.								US 5861330	